

Abstract

The present invention relates to a lithography system comprising:

- means for generating a plurality of light beamlets, and
- 5 - an electron source, arranged to be illuminated by said light beamlets, said electron source comprising a plurality of converter elements at an element distance from each other for converting a light beamlet impinging onto it into an electron beamlet directed towards and focussed on an object plane, said lithography system further comprising control means for manipulating the
- 10 mutual positions of the light beamlets with respect to the converter elements.

These control means can be of optical, thermal, mechanical or magnetical nature, and work on for instance the micro lens array, the converter plate, and the mask.